

# MID Technologies

## MID技术

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Innovative Plating Solutions for LDS MIDs

创新的LDS MID电镀液

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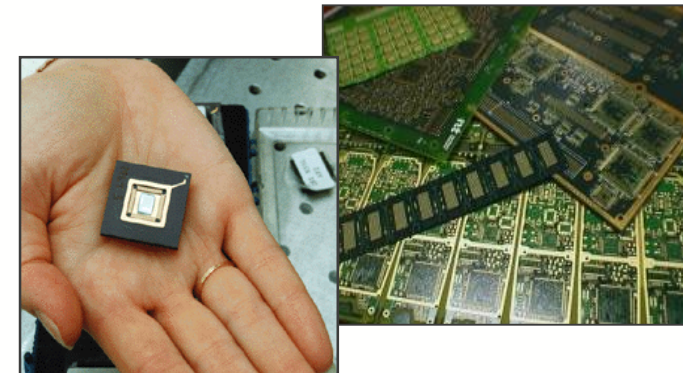
# MacDermid Alpha Electronics Solutions

- Over 2000 Worldwide Employees in 23 Countries 遍及23个国家有超过2000名员工
- Over 3500 Customers Served Worldwide by Direct Sales/Service Organizations 全球直接销售/服务3500客户
- Regional Centers of Expertise 区域专业中心

## *Industrial Solutions 工业药水*

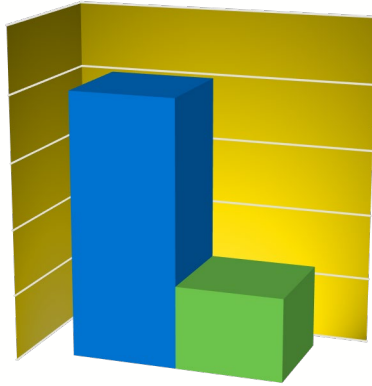


## *Electronics Solutions 电子药水*

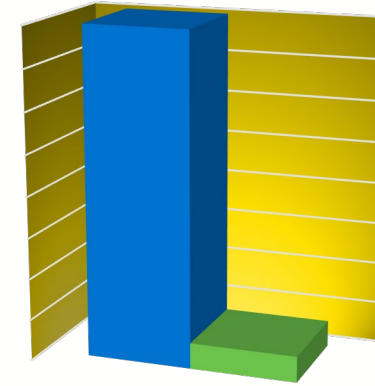


# Our Commitment to Technology

## 致力于技术开发



■ 2014 EBITDA  
■ 2014 R&D Investment



■ 2014 Revenue  
■ 2014 R&D Investment



In 2014, We spent an industry-leading **7.8%** of our revenue on R&D

在2014年，我们收入的7.8 %在研发上，是业界领先的技术

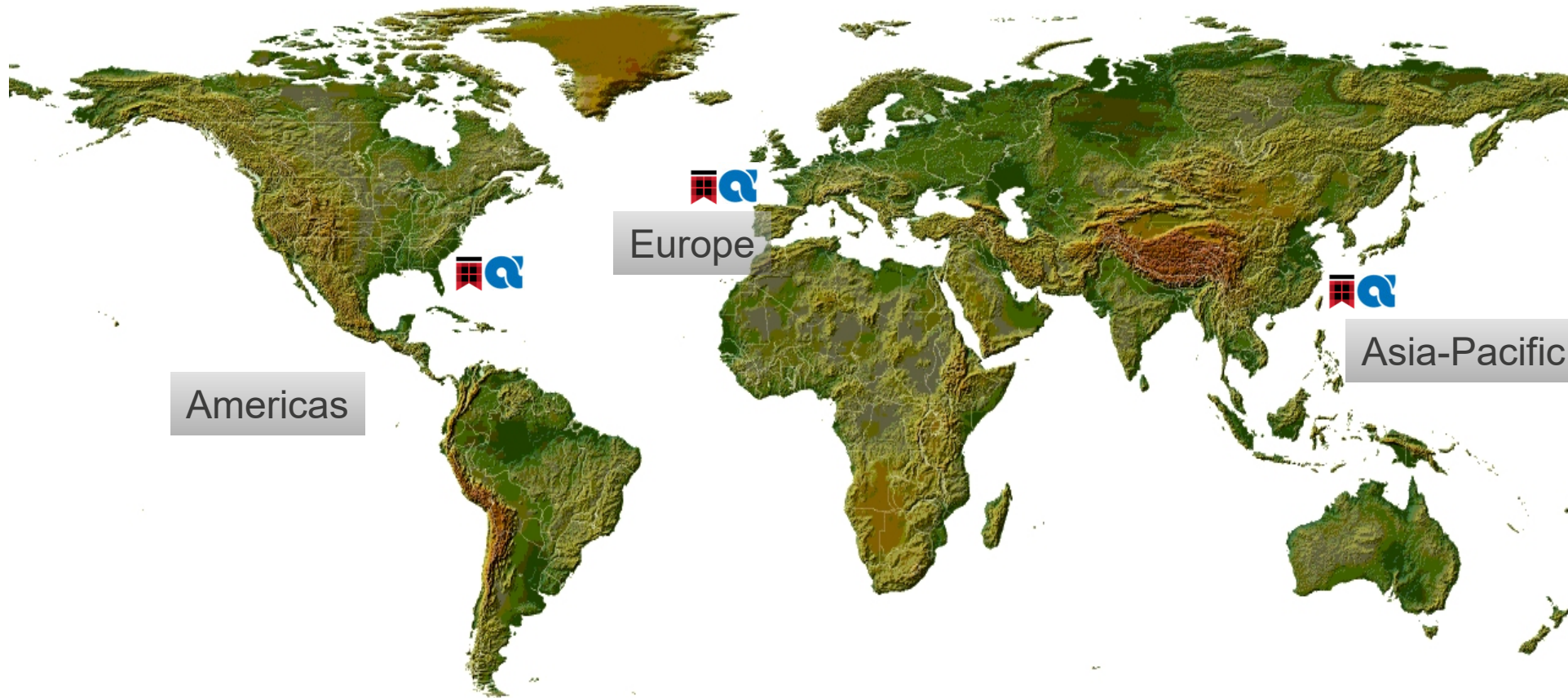


# Electronics Solutions Enabling Technology

## 电子药水的使能技术



# Worldwide Coverage 全球覆盖



- Our regions of MID expertise
- 的区域MID技术中心

# MID Piloting Capabilities in Technical Center

## MID在技术中心的试点能力



- Modern, clean, and well-equipped facility serving as “proof source” for MacDermid global research and as key demonstration site for key customers and OEMs. 现代化、清洁、设备齐全的设施作为“工艺确认”，我们的全球研究和作为重点客户和OEM厂商的示范。



- Small scale (40 liter) barrel piloting dedicated to electroless copper MID plating enables fast confirmation of developments combined with close to real-world loading and plating Conditions 小规模(40升)桶试点致力于化学镀铜MID电镀的快速认证, 开发和现实世界 结合紧密的装载和电镀条件

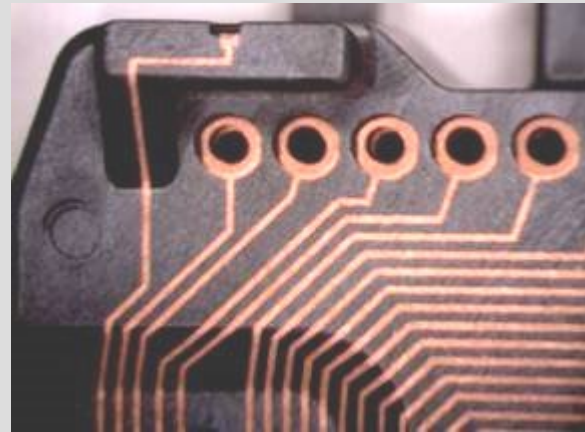
# MID Metallization Solutions

## MID金属化药水

Plating on Plastics  
Used for Decorative  
and Functional  
coatings 用于装饰与  
功能性涂层的塑料电镀



Electroless Copper for Electronics 电子化学镀铜



A combined expertise in POP and electronics plating applications remain crucial in the development and optimization of MID plating processes. POP和电子电镀综合技能对于MID电镀工艺的开发和优化很关键。

- A “Merger” of Surface Finishing Innovations  
表面精加工创新的“合并”

# MID Technology MID技术

## ■ Molded Interconnect Device (MID)

- Defined as an injection molded thermoplastic substrate which incorporates a conductive circuit pattern 定义为注塑成型的热塑性塑料基体结合了导电电路图案
  - integrating mechanical and electrical functions 结合机械和电气功能

## ■ Today's Market 现今的市场

- Growth in MID is a result of advances in plastic materials, the development of Laser Direct Structuring (LDS) and plating process availability. MID增长是塑料材料、激光直接成型和电镀工艺发展进步的结果 (LDS)
  - Majority of production volume still remains in antennas for mobile communication devices including mobile phones, laptops, tablets, etc.
  - 大部分生产量仍停留在天线的移动通信设备, 包括移动电话, 笔记本电脑, 平板电脑, 等等。

## ■ Growth opportunities in additional markets 在其他市场的成长机会

- Automotive, medical, lighting, consumer goods 汽车, 医疗, 照明, 消费品
- Opens up capabilities in design and function 开辟了在设计和功能的能力
- New options for miniaturization for form and fit 小型化的外形和和装配



Smart phones



Laptops



Medical



Lighting



Automotive



# Industry Drivers and Trends

## 工业驱动和趋势

- Fine Pitch Technology 细线间距技术
  - Opens design capabilities 开阔设计能力
  - Miniaturization 微型化
- SMT Capability SMT能力
  - Reflow resistant plastics 耐回流焊塑料
  - Solderable surface finishes 可焊镀层
- Wire bond capability 打线能力
  - Proper choice of plastics, plating thickness, surface roughness and final finish 适当选择的塑料, 电镀的厚度, 表面粗糙度和最终镀层
- Lighter design 轻量化设计
  - Integrating circuitry with existing part to reduce number of components 集成电路与现有的部分, 以减少部件的数目
- Power and Style 电源和造型
  - Integrating circuitry to provide opportunities for future designs 集成的电路来提供未来的设计机会

# Copper Innovations

## 镀铜液的创新



- Improved surface roughness 改善表面粗糙度
  - MID Copper X1 process MID铜X1
  - Better surface appearance, smoother deposit 更好的表面外观, 平整的镀层
  - Improved SMT and wire bond performance 改进SMT和引线键合性能
- Fast plating speed 快速电镀
  - MID Copper 100 XD process MID铜100 XD
  - 50% reduction in plating time 电镀时间减少50 %
- Improved Adhesion to emerging plastics 改进新兴塑料的结合力
  - MID Copper 100 XD process MID铜100 XD制程
  - Enhanced adhesion to PC substrates 增强于PC基材的结合力
- Improved manufacturing plating process 改进的电镀工艺
  - MID Copper 100 XB process MID铜100 XB制程
  - Optimized plating capability on LDS substrates 优化在LDS基材的电镀能力
  - Initiation, stability = high yields, lower cost 触发快, 稳定 = 产量高, 成本低

# Improved manufacturing performance

## 改善生产性能

- MID Copper 100 XB process provided industry with MID铜100 XB为行业提供
  - A novel Strike copper process 一种新型的冲击铜工艺
    - Complete uniform initiation on LDS substrates LDS 基材的均匀覆盖
    - Consistent predictable plating rates 一致的电镀率
    - Stable process chemistry, long bath life 稳定的工艺化学, 槽液寿命长
    - Eliminated skip plating issues 消除漏镀问题
- A novel Build copper process一种新型的沉厚铜工艺
  - Consistent predictable plating rates 一致的电镀率
  - Stable process chemistry, long bath life 稳定的工艺化学, 槽液寿命长
  - Eliminated overplating (extraneous) issues 消除溢镀(毛边)的问题
  - Fully analyzable stabilizer package 可分析的稳定剂

# MID Copper 100 XB - Key MID Plating Priorities

## MID铜100 XB - 关键MID电镀重点

Common issues effecting manufacturing yields  
影响生产良率的常见问题



Skip plating 漏镀



Overplating 溢镀



Tank plateout 槽液析出


Development 开发




Results 成果

 Yields  
产率

 Productivity  
生产效率

 Ease of Use  
易用性

 Operating Cost  
运营成本

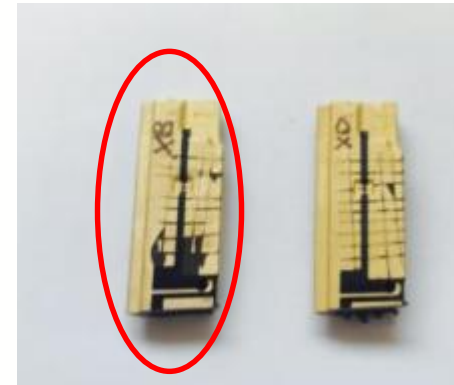
# Improved Adhesion 更好的结合力

- MID manufacturers began to migrate from PC/ABS to PC substrates. MID厂商开始从PC/ABS材料迁移到PC基材。
- PC (polycarbonate) substrates offer improved impact resistance. PC(聚碳酸酯)基材改进耐冲击性能。
- Challenges with adhesion of the plated deposit began to be reported. 与镀层的结合力面临挑战。
- MID Copper 100 XD process developed to provide improved adhesion to PC MID substrates MID铜100 XD的开发专为PC MID基材提供更好的结合力。

# XB Sample XB样品



Cu grain structure after peroxide etch.  
Light Adjusted for Plastic



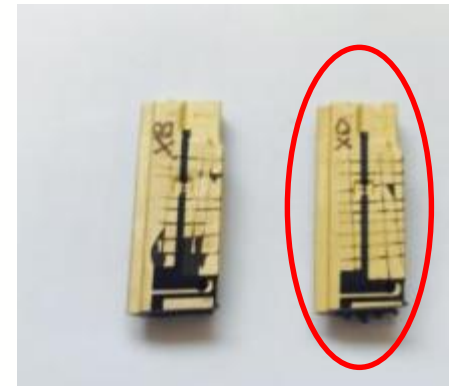
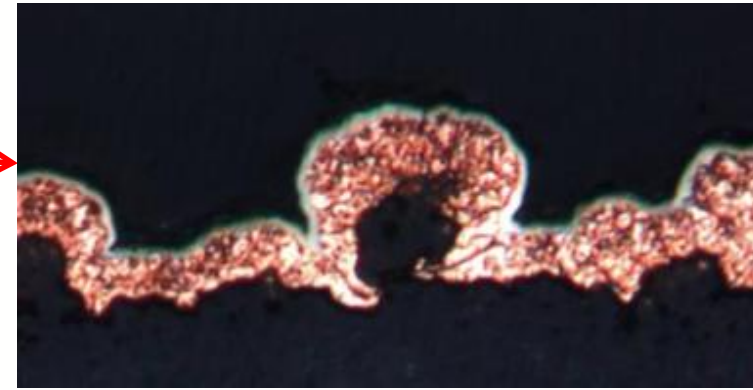
- Note delamination within PC substrate due to plating chemical attack. 由于电镀化学的侵蚀，在PC基材内出现剥离。
- Associated with failed tape testing. 导致胶带测试的失败。

# XD Sample XD样品



Cu grain structure after peroxide etch.

Light Adjusted for Plastic



- No visible signs of delamination within LDS PC substrate. PC基材内没有明显的内分层迹象。
- Improved adhesion verified by industry standard tape testing. 行业标准的胶带测试验证了改善的结合力。

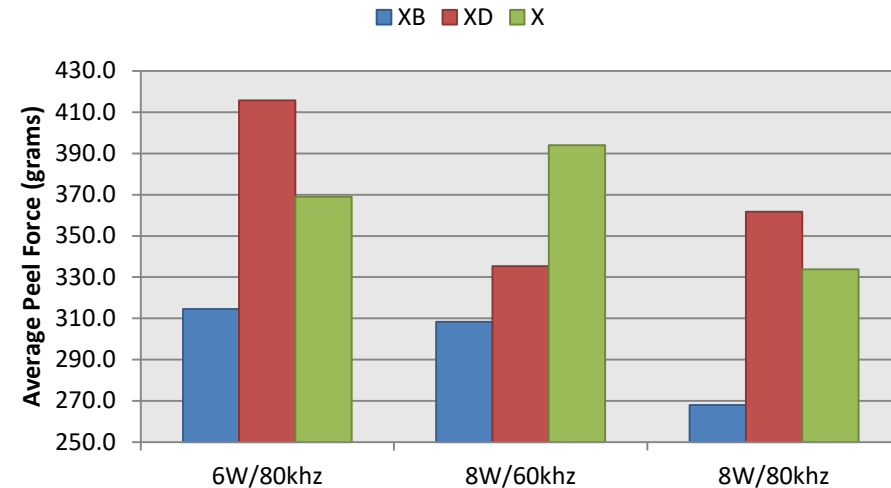
# Improved Adhesion 改善结合力



Digital Peel Test – XYZTEC Condor

## MID Cu Formulations - Peel Force vs. Laser Condition

MID铜配方 - 剥离力 vs. 激光条件



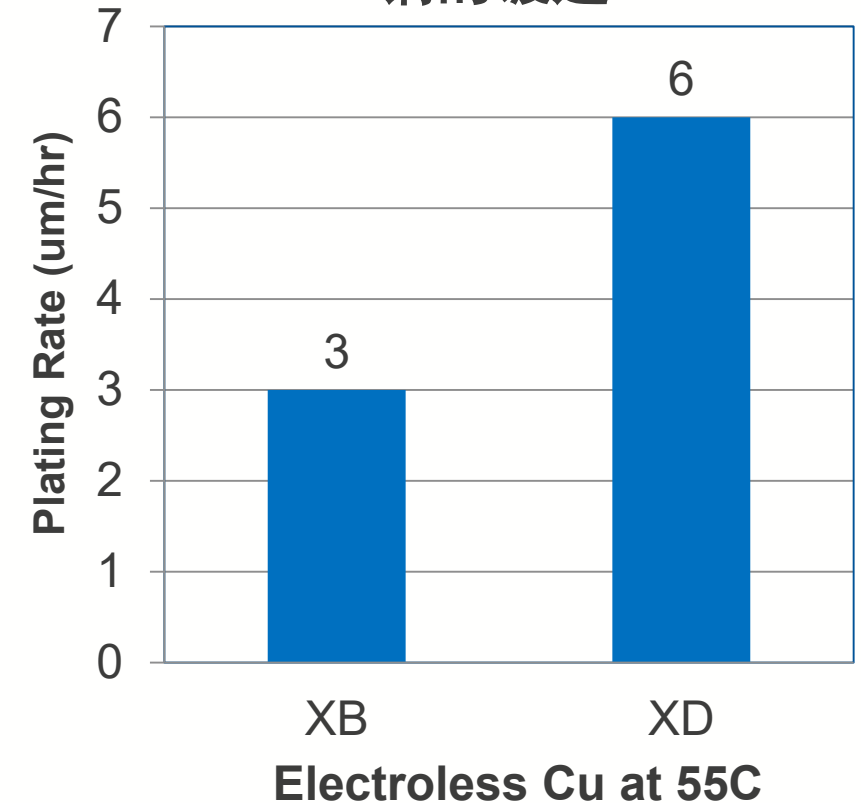
- Adhesion of electroless Cu is quantitatively tested using a highly sensitive digital pull apparatus. 铜的结合力可以使用一个高度敏感的电子数显拉力装置定量检测。
- MID XD and X1 copper have improved adhesion on PC plastics with all commonly utilized laser structuring powers. MID XD和X1铜改善对PC塑料的结合力



# Improved Speed 提高速度

- Responding to demands for increase throughput. 响应对提高产量的需求
- MID Copper XD process doubled the plating speed without negative impact on stability or bath life. MID铜XD电镀速度提高一倍, 不影响溶液稳定性或槽液寿命。
- Further increase production output without negative impact on quality. 进一步提高产量, 不影响质量。
- Lower overall running cost by maintaining stability and high speed. 通过保持稳定性和高速性降低整体运行成本。

Plating Rate of Cu Bath  
铜的镀速

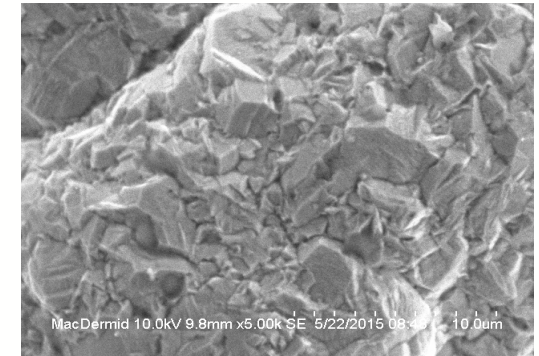
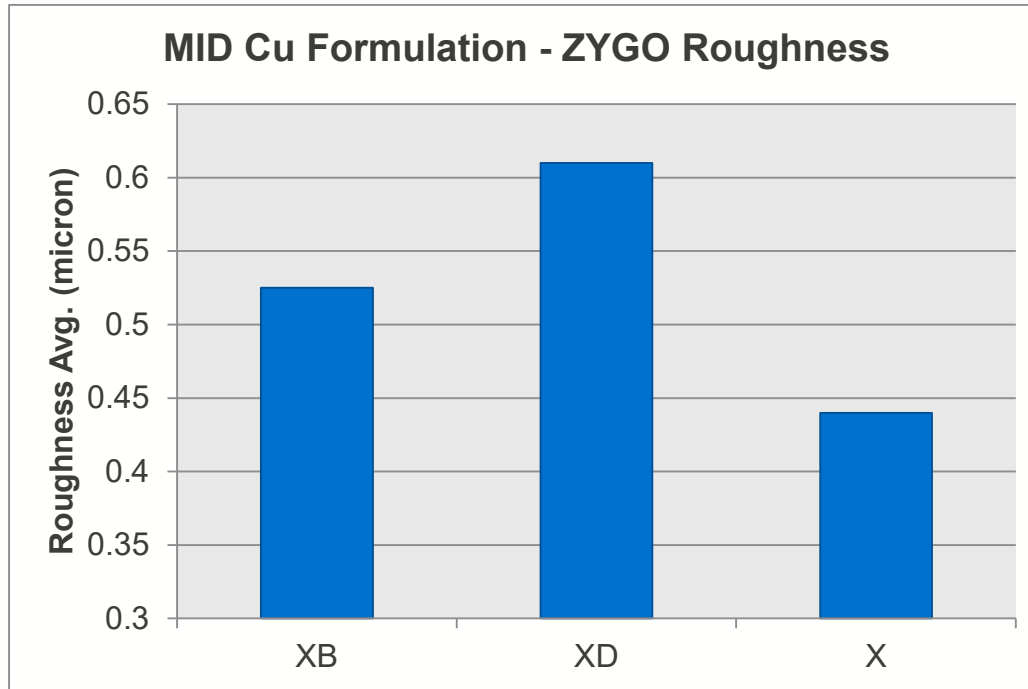


# Improving Surface Roughness

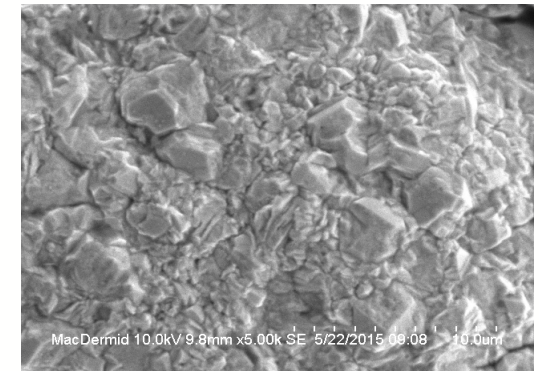
## 改善表面粗糙度

- Surface roughness can be a challenge as MIDs are used in new applications. 表面粗糙度可以是MID的新应用的一个挑战
- Roughness of the plated deposit may affect SMT and wire bonding requirements. 镀层粗糙度会影响表面贴装和引线键合的要求。
- Plated deposit roughness is linked to the roughness of the activated plastic. 镀层粗糙度与活化塑料的粗糙度有关
- LDS surfaces are rougher than DS surfaces LDS表面比DS表面粗糙
- MID Copper X1 process provides a smoother, fine grain, and “shiny” copper deposit MID铜X1提供了一个平滑的, 细晶的“闪亮”铜层。

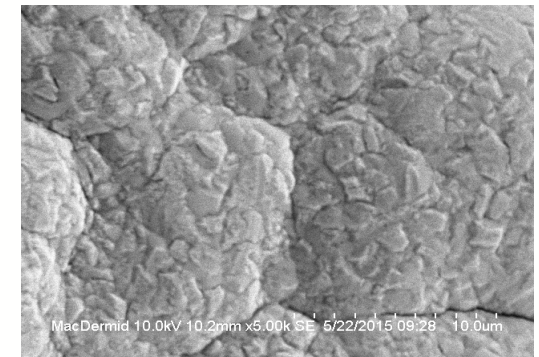
# Improved Surface Roughness 改善表面粗糙度 MacDermid Enthone



XB



XD

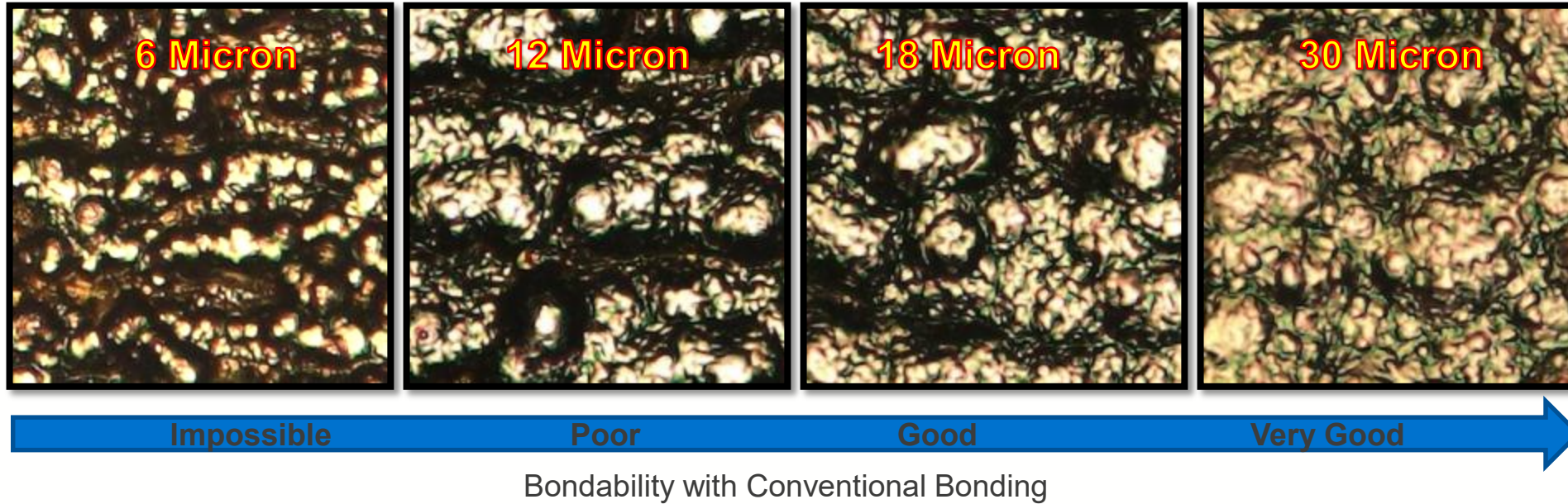


X1

- MID X1 Copper has a lower surface roughness than previous MID Cu formulations. MID X1铜具有比以前的MID铜配方较低的表面粗糙度。
- MID X1 Copper has the same improved adhesion as XD combined with the surface smoothness needed for attractive cosmetics. MID X1铜具有如XD相同的结合力，而且表面光滑。

# Benefit of Improved Surface Roughness

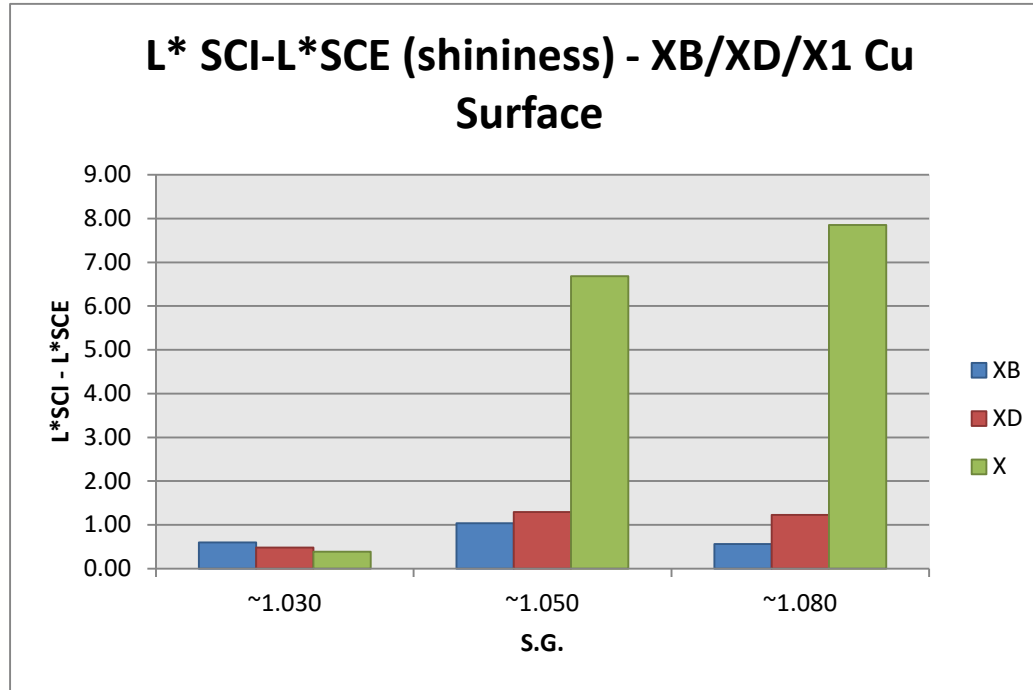
## 改进的表面粗糙度的好处



- Optical microscope shows the surface gets visibly smoother as Cu thickness increases. 光学显微镜显示铜厚度增加,表面变得明显更光滑。
- Conventional wire bonding improves with smoothness. 表面越光滑,打线力提高。

# Improved Surface Reflectivity

## 更好的表面反射率



Konica Minolta CM-2600d  
Spectrophotometer

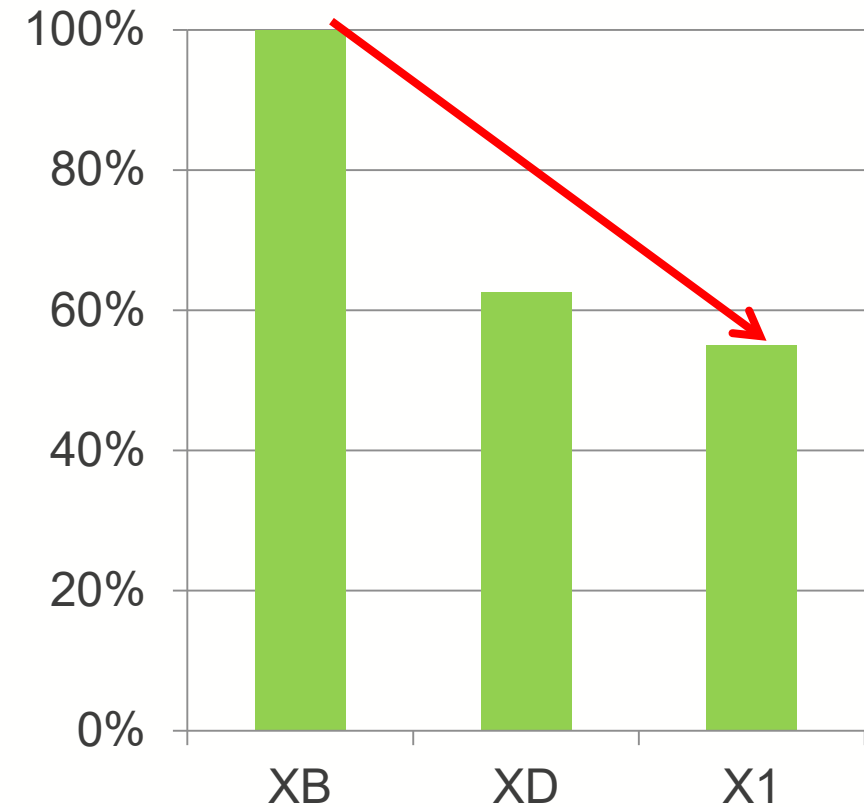
- MID X-Copper has improved glossy surface appearance vs. older formulations.  
 MID的X铜对表面外观有所改善，光泽优于旧配方

# Improved Running Cost

## 改善操作成本

- Continuous product development leading to reduced running cost. 不断的产品开发从而降低了操作成本。
- Lower running cost achieved through improved speed and optimized running conditions and extended bath life. 通过提高速度和优化电镀条件，延长槽寿命达到降低运行成本
- Maintain high yield! 维持高良率！

**Relative Running cost**  
相对操作成本

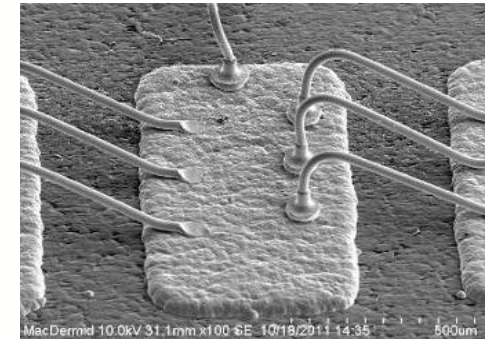
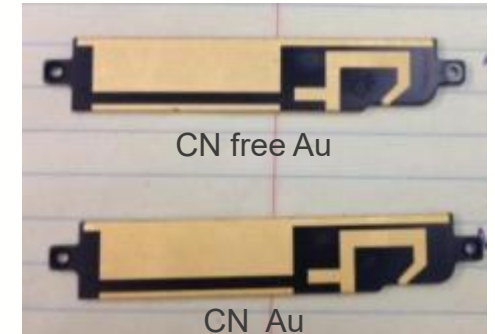


# Innovations in Final Finishes

## 在表面镀上的创新

OUR INNOVATIONS

- MID Gold 100 CF MID金100 CF
  - A true CN free gold finish 一个真正非氰镀金工艺
  - Low operating temp, 40C 较低的工作温度, 40°C
  - Neutral pH 中性pH
- MID Palladium 100 MID钯100
  - Wire bondable finish for emerging MID applications 用于新兴的MID打线应用
- MID Silver 100 MID银100
  - Low cost alternative to ENIG 替代ENIG低成本选择
  - Excellent solderability 优良的可焊性
  - Non cyanide process 非氰工艺



# There Are No Limits to MID

## MID没有止境

